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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/624,678	07/23/2003	Hikaru Sugita	5988-054-27	6692
7590 07/22/2004			EXAMINER	
Supervisor, Patent Prosecution Services			LEE, RIP A	
PIPER RUDNICK LLP			ART UNIT	PAPER NUMBER
1200 Nineteenth Street, N.W.			THE CITE	
Washington, DC 20036-2412			1713	

DATE MAILED: 07/22/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/624,678	SUGITA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Rip A. Lee	1713				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address						
Period for Reply	/ 10 000 TO 5 VOIDE 0 1 40 NTI 1/	(a) FD 014				
 A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period versions are period to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). 	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on	·					
2a) This action is FINAL . 2b) ⊠ This	action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
 4) Claim(s) 1-10 is/are pending in the application 4a) Of the above claim(s) is/are withdray 5) Claim(s) 1-4 and 7 is/are allowed. 6) Claim(s) 5 and 8 is/are rejected. 7) Claim(s) 5,6,9 and 10 is/are objected to. 8) Claim(s) are subject to restriction and/or 	wn from consideration.					
Application Papers						
9) The specification is objected to by the Examine						
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	ts have been received. Is have been received in Applicate or the contract of	ion No ed in this National Stage				
Attachment(s) 1) Notice of References Cited (PTO-892)	4) Interview Summary					
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 	Paper No(s)/Mail D 5) Notice of Informal F 6) Other:	Patent Application (PTO-152)				

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DETAILED ACTION

Claim Objections

- 1. Claim 5 is objected to because of the following informalities: Change "The antireflection" to "An antireflection." Appropriate correction is required.
- 2. Claims 6 and 9 are objected to under 37 CFR 1.75(c) as being in improper, multiple-dependent form because it makes reference to two sets of claims to different features. See MPEP § 608.01(n). Accordingly, claim 6, as well as dependent claim 9, have not been further treated on the merits.
- 3. Claim 10 is objected to under 37 CFR 1.75 as being a substantial duplicate of claim 7. When two claims in an application are duplicates or else are so close in content that they both cover the same thing, despite a slight difference in wording, it is proper after allowing one claim to object to the other as being a substantial duplicate of the allowed claim. See MPEP § 706.03(k).

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Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

5. Claims 5 and 8 are rejected under 35 U.S.C. 102(b) as being anticipated by JP 6-161111 to Murata *et al*.

The present claims are drawn to a film-forming composition comprising a polymer having a structural unit represented by general formula (4) and solvent. Murata *et al.* discloses radiation sensitive resin compositions comprising units derived from styrene substituted with –CH₂OCOOR and –CH₂OCH₂CH₂COOR groups (see structures on page 4). Since the present claim indicates that substituent R⁴ is a monvalent organic group, the structures presented in Murata *et al.* adequately satisfy the structural limitations set forth in the claims. Solvents are discussed in paragraph [0057], and compositions of polymer and solvent are used to cast resist films on silicon wafers (paragraph [0059]). Use of acid generating compounds is discussed extensively on pages 8 and 9. In sum, all aspects of the present claims is taught adequately in the prior art of Murata *et al.*

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6. Claims 5 and 8 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 5,654,121 to Eichorn *et al*.

The present claims are drawn to a film-forming composition comprising a polymer having a structural unit represented by general formula (4) and solvent. Eichorn $et\ al$. teaches a binder based on poly(4-hydroxymethylstyrene) (claim 8). The polymer satisfies the structural requisites of formula (4) in that R^4 is hydrogen and n=0. According to the practice of the invention, the binder is spin coated onto anodized aluminum plates (see example 6). As can be seen in the table, the coating solution contains solvent (in this case, methyl ethyl ketone), and it is clear that the solution forms a film. Finally, the composition also contains an acid-forming compound (claims 9-12). As such, all aspects of present claims 5 and 8 are described in Eichorn $et\ al$.

Allowable Subject Matter

7. The following is a statement of reasons for the indication of allowable subject matter: Claims 1-4 and 7 are allowed over the cited prior art (see PTO-892). None of the references which qualifies as prior art teaches or fairly suggests compounds of general structures (1) and (2). It follows that polymers (3) derived therefrom are also not taught in the prior art.

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Prior Art

7. The prior art made of record but not relied upon is considered pertinent to the Applicant's disclosure.

Carpino *et al.* (*J. Org. Chem.*, 1964) discloses the compound 5,6-acenaphtylenedimethanol. This compound is analogous to that of claim 2 except there are two hydroxymethyl groups instead of only one, as claimed.

The following references have been cited to show the state of the art with respect to polymers of acenapthylene.

U.S. Patent No. 4,604,438 to Beuhler et al.	JP 58-38711
U.S. Patent No. 4,373,046 to Hagiwara et al.	JP 57-135818
U.S. Patent No. 4,093,678 to Bailey et al.	JP 56-122862
U.S. 2002/0086934 to Kawaguchi et al.	JP 3-100005
JP 61-285233	JP 2002-3543

The following references teach to polymers containing units derived from hydroxymethylstyrene.

U.S. Patent No. 5,866,659 to Chung et al.

U.S. Patent No. 5,629,393 to Varshney et al.

U.S. Patent No. 4,569,963 to Hisaki et al.

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Information Disclosure Statement

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8. The information disclosure statement cites EP 1 205 805 to Kawaguchi et al. The

patent has also been cited in a European search report as an "X" reference against the

present claims. Closer inspection reveals that whereas the present claims requires at least

a methylene group bonded to the acenaphtylene ring (i.e., hydroxymethyl, -CH₂OH), the

compounds in the prior art contain heteroatom-containing substituents bound directly to

the carbocyclic skeleton (i.e., hydroxy, -OH). Clearly, the compounds are not the same,

and therefore, the present invention can not be anticipated by Kawaguchi et al.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Rip A. Lee whose telephone number is (571)272-1104.

The examiner can be reached on Monday through Friday from 9:00 AM - 5:00 PM. If

attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

David Wu, can be reached at (571)272-1114. The fax phone number for the organization

where this application or proceeding is assigned is (703)872-9306.

Information regarding the status of an application may be obtained from the Patent Applications Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status

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Center (EBC) at 866-217-9197 (toll free).

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July 16, 2004

DAVID W. WU SUPERVISORY PATENT EXAMINER

TECHNOLOGY CENTER 1700